

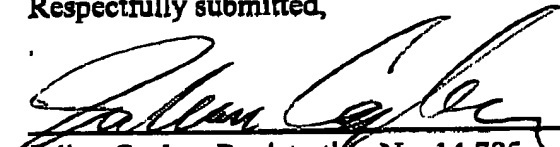
1. The Examiner objected to apparatus claims including as positive elements the wafer, the electrolyte and the plating parameters. Hence claim 19 has been completely rewritten as claim 39 to recite only structure which is positive. This claim certainly is allowable over the only prior art applied in that Kishi, among other distinctions, does not rotate the wafer holder and reservoir relative to each other.

2. Applicant wished to present method claims to bring out the distinguishing features of claim 19 which involved what the Examiner considered to be non-positive parts of the structure. This has been done in method claims 43 and 56. Again, these claims are distinguishable from the art of record.

Remaining in this application are independent apparatus claim 39 and dependent claims 20, 23, 25-30, 41 and 42, independent apparatus claim 31 and dependent claims 32-38, and independent method claim 43 and dependent claims 42-56.

In summary, the remaining claims are 20, 23, 25-56. Allowance is requested.

Respectfully submitted,



Julian Caplan, Registration No. 14,785

FLEHR HOHBACH TEST ALBRITTON & HERBERT LLP  
4 Embarcadero Center, Suite 3400  
San Francisco, CA 94111-4187  
Telephone: (650) 494-8700 Fax: (650) 494-8771